L Number	Hits	Search Text	DB	Time stamp
1	41	(US-6743695-\$ or US-6682985-\$ or	USPAT;	2004/10/05 09:20
-		US-6180490-\$ or US-6100163-\$ or	US-PGPUB	2004, 10, 03 03:20
		US-6074954-\$ or US-6495903-\$ or	100 10102	
		US-6180995-\$ or US-6287931-\$ or		
1		US-6221727-\$ or US-6770537-\$ or		
1		US-6756653-\$ or US-6413827-\$ or		
		US-6486061-\$ or US-6383913-\$ or		
		US-6348407-\$ or US-6716742-\$ or		
		US-6399432-\$ or US-6693011-\$ or		
		US-6689664-\$ or US-6521923-\$ or		ì
		US-6686627-\$ or US-6153905-\$ or		1
		US-5869875-\$ or US-5918137-\$ or	1	
		US-6215152-\$ or US-6091110-\$).did. or		
	1	(US-5949104-\$ or US-5841166-\$ or		
		US-5252848-\$ or US-6271552-\$ or		
		US-6190978-\$ or US-6222233-\$ or		
		US-6048772-\$ or US-6034415-\$ or		
		US-5900663-\$ or US-6716770-\$).did. or		
		(US-20040069410-\$ or US-20040166240-\$ or		
		US-20040156987-\$ or US-20040023453-\$ or		
		US-20030129827-\$).did.		
2	8	((((silicon near1 precursor) and (cvd	USPAT;	2004/10/05 09:37
		(chemical near1 vapor near1 deposition)))	US-PGPUB;	, , , , , , , , , , , , , , , , , , , ,
		and (low near1 dielectric)) and (cmp	EPO; JPO	<b>i</b>
		(chemical near1 mechanical near1		
		polishing))) and (omcts		
		octamethylcyclotetrasiloxane tmcts		
		tetramethylcyclotetrasiloxane)		
3	106	(((precursor and (cvd (chemical near1	USPAT;	2004/10/05 09:37
		vapor nearl deposition))) and (low nearl	US-PGPUB;	
		dielectric)) and (cmp (chemical near1	EPO; JPO	i
		mechanical near1 polishing))) and (omcts		1
		octamethylcyclotetrasiloxane tmcts		
		tetramethylcyclotetrasiloxane)		
4	17	' ' '   F ' ' '	USPAT;	2004/10/05 09:37
		(chemical near1 vapor near1 deposition)))	US-PGPUB;	
		and (low near1 dielectric)) and (cmp	EPO; JPO	
		(chemical near1 mechanical near1		1
		polishing))) and (omcts		1
		octamethylcyclotetrasiloxane tmcts		
_		tetramethylcyclotetrasiloxane)		
5	9	(((((silicon near3 precursor) and (cvd	USPAT;	2004/10/05 09:37
		(chemical near1 vapor near1 deposition)))	US-PGPUB;	
		and (low near1 dielectric)) and (cmp	EPO; JPO	
		<pre>(chemical near1 mechanical near1 polishing))) and (omcts</pre>		
		octamethylcyclotetrasiloxane tmcts		
		tetramethylcyclotetrasiloxane)) not		
		(((((silicon near1 precursor) and (cvd		
1		(chemical near1 vapor near1 deposition)))		
		and (low near1 dielectric)) and (cmp		
		(chemical near1 mechanical near1		
		polishing))) and (omcts		
		octamethylcyclotetrasiloxane tmcts		
		tetramethylcyclotetrasiloxane))		
6	14	("3510369"   "4872947"   "4895734"	USPAT	2004/10/05 09:40
'		"4951601"   "5011706"   "5086014"	331	2001, 20, 03 03.40
	İ	"5242530" "5298597" "5360491" "5465680" "5468978" "5480300"	1	
]		"6054379"   "6147009"   "2002/0111042"	1	
į į		"2003/0003765"   "2003/0003768"		
		"2003/0089988"   "2003/0111730"		
		"2003/0129827").PN.		
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